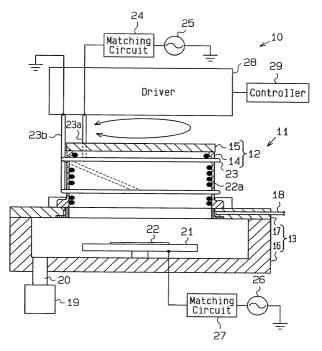
Fig.1



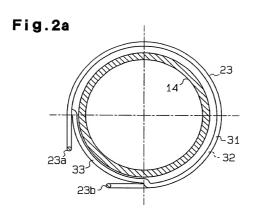
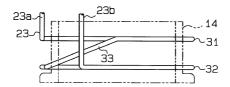
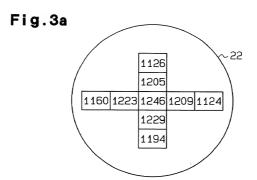


Fig.2b





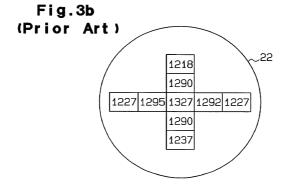


Fig.4

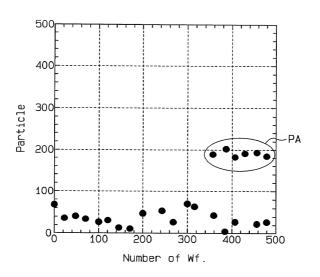
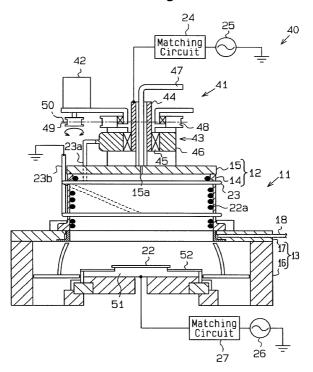


Fig.5

Numbers of wafers rotation	Rotation rate (rpm)	Number of processed wafers	Particle size	Initial particle number	Particle number after processing	Difference	TOTAL
0	0	25	S	19	26	+7	+31
			SM	1	12	+11	
			М	0	13	+13	
			L	0	0	0	
		100	SM	10	18	+8	+17
			SM	2	6	+4	
			М	3	8	+5	
			SM	0	0	0	
Approx. 3.75	Approx. 0.52	25	S	24	59	+35	+ 43
			SM	3	5	+2	
			М	6	12	+6	
			L	0	0	0	
		100	S	15	15	0	+13
			SM	2	6	+4	
			М	6	15	+9	
			L	0	0	0	
		150	S	21	5	-16	-18
			SM	0	3	+3	
			М	7	2	-5	
			L	0	0	0	
Approx. 37	Approx. 0.054	25	S	2	23	+21	+33
			SM	1	8	+7	
			М	8	13	+5	
			L	0	0	0	
		100	S	37	13	-24	- 37
			SM	15	6	- 9	
			М	15	10	- 5	
			L	0	1	+1	
Approx. 148	Approx. 0.0135	25	S	8	26	+18	+ 29
			SM	4	7	+3	
			М	13	21	+8	
			L	0	0	0	
		100	S	22	19	+3	+10
			SM	1	8	+7	
			М	3	9	+6	
			L	0	0	0	
		150	S	12	19	+ 7	+12
			SM	0	3	+3	
			М	3	5	+2	
			L	0	0	0	

Fig.6



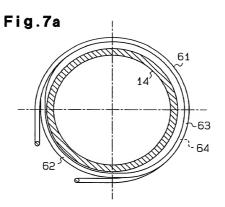


Fig.7b

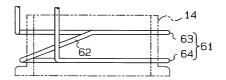


Fig. 8a

71

14

72

72

73

Fig.8b

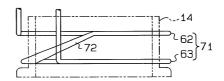


Fig.9a

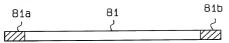


Fig.9b

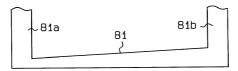


Fig.10a

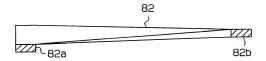


Fig.10b

